

Fig. 1. The proposed metal(In)GaAs and metal/Ge contact structure used for CTLM analysis

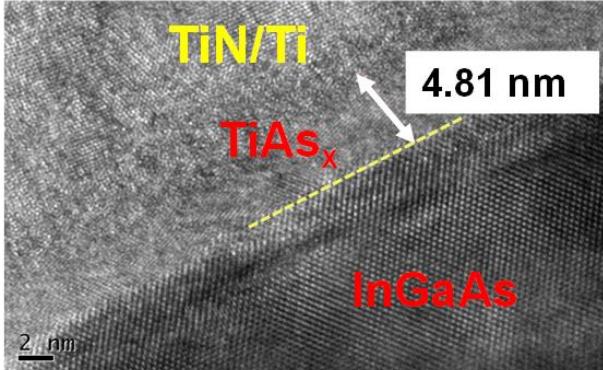


Fig. 2. TEM image of W/TiN/Ti/In_{0.53}Ga_{0.47}As structure

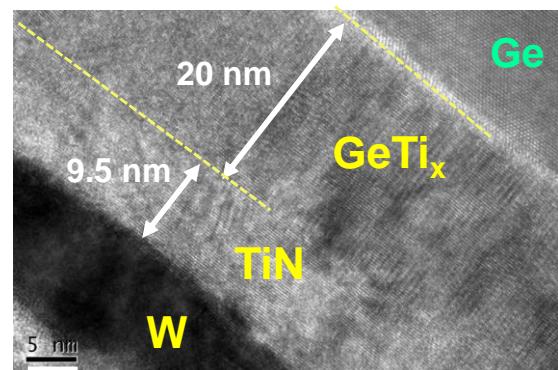


Fig. 3. TEM image of W/TiN/Ti/Ge structure

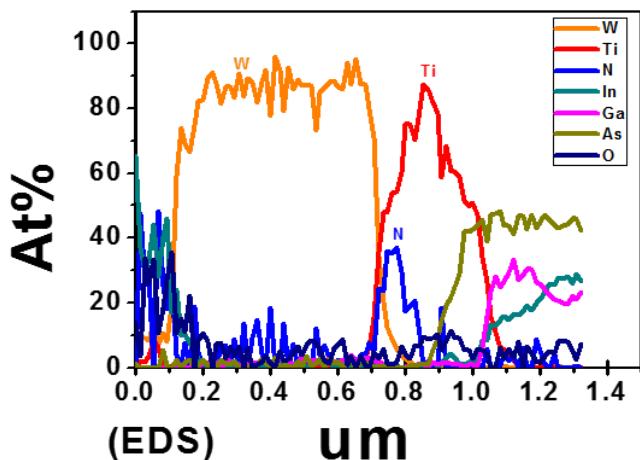


Fig. 4. EDS depth profile of W/TiN/Ti/In_{0.53}Ga_{0.47}As structure

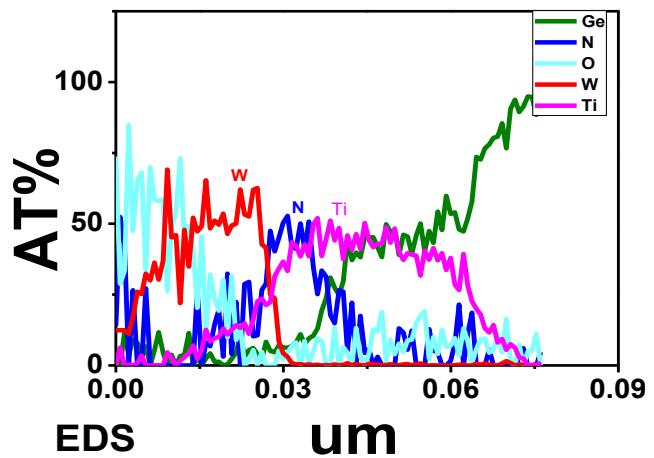


Fig. 5. EDS depth profile of W/TiN/Ti/Ge structure

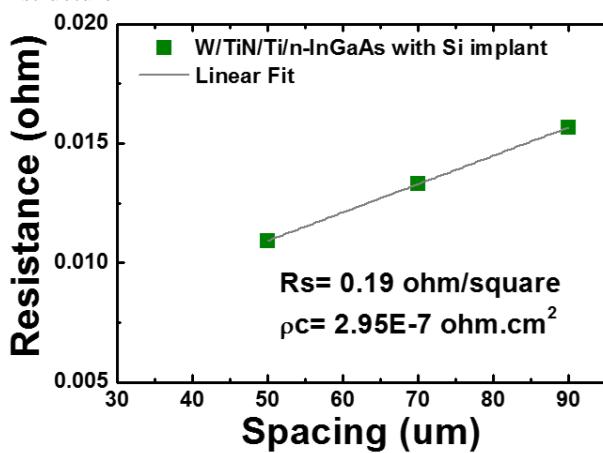


Fig. 6. Contact resistance extraction by CTLM for W/TiN/Ti/In_{0.53}Ga_{0.47}As structure

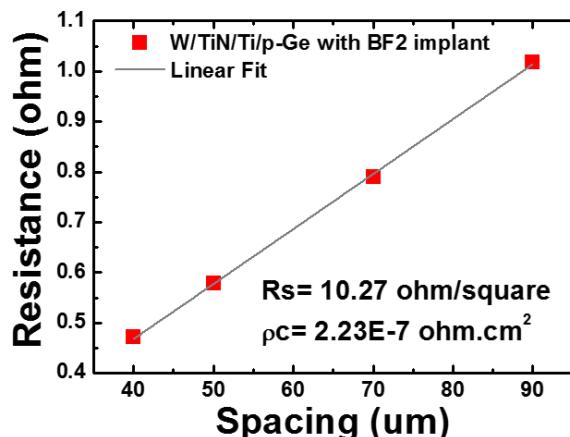


Fig. 7. Contact resistance extraction by CTLM for W/TiN/Ti/Ge structure